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	APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
	10/828,555 04/21/2004		Nobumitsu Takase	474082002600	5435
	25227	7590 05/17/2006	EXAMINER		INER
	MORRISON & FOERSTER LLP			KUNEMUND, ROBERT M	
	1650 TYSONS BOULEVARD SUITE 300 MCLEAN, VA 22102			ART UNIT	PAPER NUMBER
				1722	
				DATE MAILED, 05/17/2004	,

Please find below and/or attached an Office communication concerning this application or proceeding.

_		Application No.	Applicant(s)				
	Office Astion Occurrence	10/828,555	TAKASE ET AL.				
	Office Action Summary	Examiner	Art Unit				
_		Robert M. Kunemund	1722				
	The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply						
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).							
Status							
1)	Responsive to communication(s) filed on						
		action is non-final.					
′=	Since this application is in condition for allowar		secution as to the merits is				
,—	closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Dispositi	on of Claims						
4)⊠	Claim(s) <u>1-8</u> is/are pending in the application.						
	4a) Of the above claim(s) is/are withdrawn from consideration.						
	5) Claim(s) is/are allowed.						
·	6) Claim(s) 1-8 is/are rejected.						
·	· · · · · · · · · · · · · · · · · · ·						
	8) Claim(s) are subject to restriction and/or election requirement.						
	· ·						
Application Papers							
9) The specification is objected to by the Examiner.							
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.							
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).							
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.							
Priority under 35 U.S.C. § 119							
	 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 						
	2. Certified copies of the priority documents						
	3. Copies of the certified copies of the prior	•	d in this National Stage				
	application from the International Bureau (PCT Rule 17.2(a)).						
* See the attached detailed Office action for a list of the certified copies not received.							
Attachment(s)							
1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413)							
2) Notic	2) Notice of Draftsperson's Patent Drawing Review (PTO-948) Paper No(s)/Mail Date						
	nation Disclosure Statement(s) (PTO-1449 or PTO/SB/08)	5) Notice of Informal Page 6) Other:	atent Application (PTO-152)				
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DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

Claims 1, 4, 5 and 8 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yokota et al (5,067,989).

The Yokota et al reference teaches a method and product of a silicon wafer, note entire reference. Into a crucible, raw silicon or polycrystalline silicon is placed and melted. Then by the czochralski method, a single crystal ingot of silicon is created and the ingot is sliced to create a wafer of silicon, col.3. The impurity concentration is the single crystal silicon is less then .4 ppta, note col. 2. The sole difference between the instant claims and the prior art is the resistively range. However, in the absence of

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unexpected results, it would have been obvious to one of ordinary skill in the art to determine through routine experimentation the optimum, operable resistively of the silicon in the Yokota et al reference in order to create the desired property for semiconductor manufacture, noting, impurity levels do in fact effect this property.

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Claims 2 and 6 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yokota et al (5,067,989) in view of Fuerhoff et al (6,454,851).

The Yokota et al reference is relied on for the same reasons as stated, supra, and differs form the instant claims in the formation of the polycrystalline silicon.

However, the Fuerhoff et al reference teaches growing polycrystalline silicon for single crystal growth, by the Siemans method using trichlorosiliane, note col. 3. It would have been obvious to one of ordinary skill in the art to modify the Yokota et al reference by the teachings of the Fuerhoff et al reference to use polycrystalline silicon made my the Siemans process in order to lower metal impurities in the silicon.

Claims 3 and 7 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yokota et al (5,067,989) in view of Fuerhoff et al (6,454,851).

The Yokota et al and Fuerhoff et al references are relied on for the same reasons as stated, supra, and differs form the instant claims in the source gas of the polycrystalline silicon. However, in the absence of unexpected results, it would have been obvious to one of ordinary skill in the art to determine through routine experimentation the optimum, operable source gas of the silicon in the Yokota et al reference in order to lower all impurities in the final silicon.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Robert M. Kunemund whose telephone number is 571-272-1464. The examiner can normally be reached on 8 hours.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Yogendra Gupta can be reached on 571-272-1312. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Robert M Kunemund Primary Examiner Art Unit 1722

RMK